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(54) Title: BACKSIDE REACTIVE INHIBITION GAS

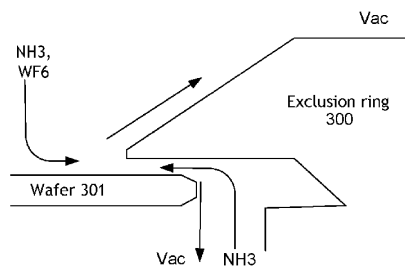


FIG. 3C

(57) Abstract: Provided herein are methods and apparatuses for controlling uniformity of processing at an edge region of a semiconductor wafer. In some embodiments, the methods include providing a backside inhibition gas as part of a deposition-inhibition-deposition (DID) sequence.

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